DECLARATION

As a below named inventor, we hereby declare that:

Our residence, post office address and citizenship are as stated below next to our names.

We verily believe we are the joint inventors of the invention entitled: METHOD AND DEVICE TO REDUCE GATE-INDUCED DRAIN LEAKAGE (GIDL) CURRENT IN THIN GATE OXIDE MOSFETs (Docket No. MIO 0054 PA/98-0771), described and claimed:

X_	in the attached specification;	
<u> </u>	in the specification filed	_, as U.S. Application Serial No
	, and as amended	······································

We hereby authorize the attorney(s) and/or agent(s) appointed herein to indicate above whether the invention is described and claimed in an attached specification and to provide the Filing Date and Serial No. of the corresponding U.S. Application, if previously filed.

We hereby state that we have reviewed and understand the contents of the above identified specification, including the claims as filed and as amended by any amendment referred to above.

We acknowledge the duty to disclose to the Patent and Trademark Office all information known to me to be material to patentability as defined in Title 37, Code of Federal Regulations, §1.56(a).

We further declare that all statements made herein of our own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under §1001 of Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Inventor's signature \(\).	(Wy			
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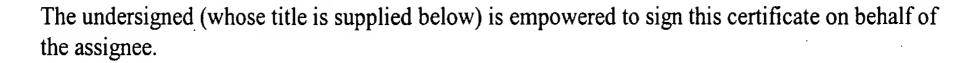




POWER OF ATTORNEY

Applicants: Chandra V. Mouli and Ceredig Roberts
Application No.: Filed:
Entitled: METHOD AND DEVICE TO REDUCE GATE-INDUCED DRAIN LEAKAGE
(GIDL) CURRENT IN THIN GATE OXIDE MOSFETs (Docket MIO 0054 PA/98-0771)
(OBE) CORRENT IN THIN ONLE ON DE MODI ETS (DOCKET MIO 003417070-0771)
\cdot
CERTIFICATE UNDER 37 CFR 3.73(b)
Micron Technology, Inc., a corporation of the State of Delaware, with a place of business at 8000 S. Federal Way, Boise, ID 83706-9632 certifies that it is the assignee of the entire right, title and interest in the patent application identified above by virtue of either:
A. [X] An assignment from the inventor(s) of the patent application identified above, a copy of which is attached.
OR
B. [] A chain of title from the inventor(s), of the patent application identified above, to the current assignee as shown below:
1. From: To:
The document was recorded in the Patent and Trademark Office at
Reel, or for which a copy thereof is attached.
2. From: To:
The document was recorded in the Patent and Trademark Office at
Reel Frame, or for which a copy thereof is attached.
3. From: To:
The document was recorded in the Patent and Trademark Office at
Reel, or for which a copy thereof is attached.
[] Additional documents in the chain of title are listed on a supplemental sheet. [] Copies of assignments or other documents in the chain of title are attached.
[] copies of assignments of other documents in the chain of the are attached.

The undersigned has reviewed all the documents in the chain of title of the patent application identified above and, to the best of undersigned's knowledge and belief, title is in the assignee identified above.



Micron Technology, Inc. hereby appoints the following attorney(s) and/or agent(s) to prosecute this application and to transact all business in the Patent and Trademark Office connected therewith:

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Micron Technology, Inc. hereby declares that all statements made herein of my own knowledge are true, and that all statements made on information and belief are believed to be true; and further, that these statements are made with the knowledge that willful false statements, and the like so made, are punishable by fine or imprisonment, or both, under Section 1001, Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Date:	8-18-00	
Name:	Michael L. Lynch	· · · · · · · · · · · · · · · · · · ·
Title:	Chief Patent Counsel	
Signature:		